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(21)Application number : **63-211404** (71)Applicant : **OLYMPUS OPTICAL CO LTD**
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(54) PRODUCTION OF THIN EL FILM AND PELLETT FOR VAPOR DEPOSITION

(57)Abstract:

PURPOSE: To uniformize the activator concn. in a luminescent film formed by vapor deposition in the thickness direction as well and to rapidly and surely produce the luminescent film having stable characteristics by pelletizing raw material powder only by pressing the powder with a pressurizing press at the time of producing a vapor deposition pellet in an electron beam vapor deposition method. CONSTITUTION: The bound body formed by applying a pressure to the powder for which the sulfide of metal is used as the base body and a transition metal is used as an activator is made into the vapor deposition pellet. This pellet is used in the electrode beam vapor deposition method. Splashing of a vapor deposition source by the instantaneous evaporation at the moment when an electron beam comes into contact with the pellet and local splashing of the gas is prevented in this way and the activator concn. distribution in the vapor deposited film is uniformized. Since the vapor deposition pellet is produced by the press, the pellet is easily produced in a short period of time.

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